



NOTES

1. COATING(S1): LOW GDD COATING
 $R_s > 99\% @ 710\text{ nm} - 900\text{ nm}, AOI = 45^\circ$
 $R_p > 99\% @ 750\text{ nm} - 850\text{ nm}, AOI = 45^\circ$
2. GDD:
 $|GDD_s| < 30\text{ fs}^2 @ 710\text{ nm} - 900\text{ nm}, AOI = 45^\circ$
 $|GDD_p| < 30\text{ fs}^2 @ 750\text{ nm} - 850\text{ nm}, AOI = 45^\circ$
3. CLEAR APERTURE(S1, S2): $> 90\% CA$
4. SURFACE QUALITY(S1, S2): $10/5(S/D)$
5. SURFACE FLATNESS(S1): $\lambda / 10 @ 633\text{ nm}$
6. PARALLELISM(S1, S2): $< 10\text{ arcsec}$
7. CHAMFER: $0.1\text{ mm}, 45^\circ$
8. THICKNESS TOLERANCE: $\pm 0.1\text{ mm}$
9. DIAMETER TOLERANCE: $+0.0\text{ mm} / -0.1\text{ mm}$
10. BACK SURFACE(S2): POLISHED

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	LZHOU	Aug./5th/24	ULTRAFAST MIRROR $\phi 12.7\text{ mm} \times 6\text{ mm}, 710\text{ nm} - 900\text{ nm}$			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	1.6 g	4:1	B